



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: $>90\%CA$
3. SURFACE QUALITY(S1, S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda / 4@633 \text{ nm(SUBSTRATE)}$
5. PARALLELISM(S1, S2): $<3 \text{ arcmin}$
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}} > 90\%, T_{\text{abs}} > 85\% @ 520-800 \text{ nm}, 45^\circ \text{ AOI}$
 $R_{\text{avg}} > 95\%, R_{\text{abs}} > 90\% @ 380-490 \text{ nm}, 45^\circ \text{ AOI}$
 AR COATING(S2): $R_{\text{abs}} < 2\% @ 520-800 \text{ nm}, 45^\circ \text{ AOI}$

DRAWING PROJECTION			LBTEK			
	NAME	DATE	DM10-505LP			
DRAWN	LZHOU	JUL./30th/24	LONGWAVE DICHOIC MIRROR $\phi 25.4 \text{ mm} \times 3.2 \text{ mm}, 505 \text{ nm}$			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	3.6 g	1:1	A